

10/564453

IAP20 Received 12 JAN 2006

SHIGA7.041APC

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Masudo et al.
Appl. No.	:	Unknown
Filed	:	Herewith
For	:	POSITIVE PHOTORESIST COMPOSITIONAL METHOD OF FORMING RESIST PATTERN
Examiner	:	Unknown
Group Art Unit	:	Unknown

PRELIMINARY AMENDMENT

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 6 of this paper.